CLAIMS

- 1. A porous-material-forming photo-curing resin composition comprising:
- a photo-polymerizable monomer (A) having a surface tension of not more than 25×10^{-5} N/cm,

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an organic compound (B) that is non-compatible with the photo-polymerizable monomer (A),

- a common solvent (C) that is compatible with the photo-polymerizable monomer (A) and the organic compound (B); and
 - a photo-polymerization initiator (D).
- 2. The porous-material-forming photo-curing resin composition according to claim 1, wherein the photo-polymerizable monomer (A) is a photo-polymerizable monomer containing a fluorine atom or a silicon atom.
- 3. The porous-material-forming photo-curing resin composition according to claim 1 or 2, wherein: the photo-polymerizable monomer (A) and other photo-polymerizable monomers are used in combination and the blending amount of the other photo-polymerizable monomers is not more than 90% by weight of the entire amount of the photo-polymerizable monomers.
- 4. The porous-material-forming photo-curing resin
 composition according to any one of claims 1 to 3, wherein

the organic compound (B) is an organic compound having a surface tension of not less than 40×10^{-5} N/cm.

5. The porous-material-forming photo-curing resin composition according to any one of claims 1 to 4, wherein the component that is non-compatible with the photopolymerizable monomer (A) is water.

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- 6. The porous-material-forming photo-curing resin composition according to any one of claims 1 to 5, wherein the common solvent (C) is an organic solvent having a surface tension in a range from 25 to 35×10^{-5} N/cm.
- 7. The porous-material-forming photo-curing resin composition according to any one of claims 1 to 6, wherein the photo-polymerizable monomer (A) has a (metha)acryloyl group or a vinyl group as a photo-polymerizable group.
- 8. The porous-material-forming photo-curing resin composition according to any one of claims 1 to 7, wherein the organic compound (B) comprises one or more kinds of groups and/or bonds selected from the group consisting of a hydroxide group, an amino group, a ketone bond, a sulfide bond, a sulfoxide bond and a cyclic amide bond.
- 9. The porous-material-forming photo-curing resin composition according to any one of claims 1 to 8, wherein the common solvent (C) is an aromatic or alicyclic hydrocarbon solvent, an oxygen-containing solvent or a nitrogen-containing solvent.

- 10. A porous resin cured product which is obtained by photo-curing the porous-material-forming photo-curing resin composition according to any one of claims 1 to 9.
- 11. The porous resin cured product according to claim 10, which is obtained by removing the organic compound (B) or water and the common solvent (C) contained therein.

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- 12. The porous resin cured product according to claim
 10 or 11, which has a film shape or a sheet shape.
- 13. The porous resin cured product according to any one of claims 10 to 12, which has a substrate on at least one face.
 - 14. A liquid crystal display element comprising the porous resin cured product according to any one of claims 10 to 13 as a supporting material.
- 15. A liquid crystal recording material comprising the porous resin cured product according to any one of claims 10 to 13 as a supporting material.